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PATENT  
Atty Docket:P70977US0

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Confirmation No.: 7626

Holger SEITZ et al.

Serial No.: 10/564,282

Group Art Unit: Not Yet Assigned

Filed: January 11, 2006

Examiner: Not Yet Assigned

For: METHOD FOR ANALYSIS OF OBJECTS IN MICROLITHOGRAPHY

**INFORMATION DISCLOSURE STATEMENT  
UNDER 37 CFR 1.97**

**MAIL STOP AMENDMENT**  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

As a continuing means of complying with the duty of disclosure under 37 CFR §1.56, and in accordance with 37 CFR §§1.97 and 1.98, Applicant through his undersigned attorney, submits this Information Disclosure Statement for the Examiner's consideration. The patents, publications or other information submitted herewith are listed on the attached Form PTO-1449. In accordance with 37 CFR §1.98(a)(2) only a copy of each foreign patent document and non-patent literature document listed on the attached Form PTO-1449 is submitted herewith.

In accordance with 37 CFR §1.97(b) this Information Disclosure Statement is being submitted before the mailing of the first Office Action on the merits and therefore, no fee is due.

The patents and publications AA-AD and AI-AL listed on Form PTO-1449 were cited in an International Search Report in counterpart Patent Application No. PCT/EP2004/007267. A copy of the Search Report is enclosed.

Serial No.: 10/564,282  
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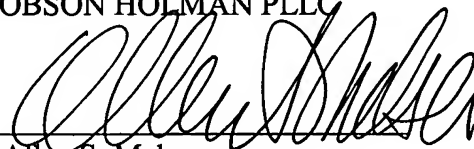
The patents and publications AB and AD-AF listed on Form PTO-1449 were also cited in an Office Action in counterpart German Patent Application No. DE 103 32 059.8. A copy of the Office Action is enclosed.

Documents AG and AH are cited in the instant specification on page 3. Document AG is also cited on page 16 of the instant specification.

It is respectfully requested that the Examiner initial and return a copy of the enclosed Form PTO-1449, and to similarly indicate in the official file wrapper of this patent application that the attached documents have been considered. If the Examiner has any questions or wishes to discuss this application, the Examiner is invited to telephone the undersigned representative at the number set forth below.

Respectfully submitted,

JACOBSON HOLMAN PLLC

By: 

Allen S. Melser

Registration No. 27,215

Date: 7/29/06

**Customer No. 00,136**  
400 Seventh Street, N.W.  
Washington, D.C. 20004  
(202) 638-6666



Form PTO-1449

# INFORMATION DISCLOSURE STATEMENT

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Filing Date:	January 11, 2006
Inventor:	SEITZ et al.
Art Unit:	Not Yet Assigned
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## U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Relevant Pages, Cols, Lines, Figs.
	AA	US- 4,633,504	12/30/86	WIHL et al.	
	AB	US- 6,272,236 B1	8/7/01	PIERRAT et al.	
	AC	US- 5,576,829	11/19/96	SHIRAISHI et al.	
	AD	US- 2002/0186879 A1	12/12/02	HEMAR et al.	
	AE	US- 2002/0041377 A1	4/11/02	HAGIWARA et al.	
	AF	US- 6,466,315	10/15/02	KARPOL et al.	
	AG	US- 5,498,923	3/12/96	LA FONTAINE et al.	
	AH	US- 6,002,740	12/14/99	CERRINA et al.	

## FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.	Country Code + Number	Publication Date	Name of Patentee or Applicant	Relevant Pages, Cols, Lines, Figs.	Translation
	AI	EP 1 081 489 A	3/7/01	KARPOL et al.		N/A

## NON-PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of author in CAPS; title of article; title of book, magazine, journal etc.; date; page(s); volume/issue number(s); publisher; city and/country where published.
	AJ	TOJO ET AL.; "Mask Defect Inspection Method by Database comparison with 0.25-0.35 $\mu$ m Sensitivity"; Japanese Journal of Applied Physics; December 1994; pgs. 7156-7162; Vol. 33 No. 12B; Tokyo.
	AK	BARTY ET AL.; "Aerial Image Microscopes for the Inspection of the defects in EUV masks"; Proceedings of the SPIE; October 2002; pgs. 1073-1084; Vol. 4889; US.
	AL	BUDD ET AL.; "A New Mask Evaluation Tool, the Microlithography Simulation Microscope Aerial Image Measurement System"; Proceedings of the SPIE; March 1994; pgs. 530-540; Vol. 2197; US.

Examiner Signature	Date Considered
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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